

Amendments to the Specification:

Please replace the paragraph at page 6, lines 11-22 with the following amended paragraph:

In the meantime, actual production of a reflective layer most often conducted will be a formation of thin films thorough a sputtering method in which a target comprising a material for a reflective layer is employed. As described above, in the silver alloy according to the present invention, the ~~iridium~~ indium and tin contained are preferentially oxidized, and oxide thus generated will act as a protective film to insure inhibition of oxidization and sulfuration, which will happen subsequently. When a reflection coating is formed with the silver alloy according to the present invention, oxygen is mixed with argon gas, which is to be introduced to a sputtering apparatus used in a sputtering method, reactive sputtering is conducted to form the reflective layer while oxidizing the same, thereby forming a protective film at an earlier stage of a reflective layer formation.